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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/642,291	08/18/2003	Shoichiro Yasunami	Q77024	2020
23373	7590	02/07/2006	EXAMINER	
SUGHRUE MION, PLLC 2100 PENNSYLVANIA AVENUE, N.W. SUITE 800 WASHINGTON, DC 20037			CHU, JOHN S Y	
			ART UNIT	PAPER NUMBER
			1752	
DATE MAILED: 02/07/2006				

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)	
	10/642,291	YASUNAMI ET AL.	
	Examiner	Art Unit	
	John S. Chu	1752	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 14 November 2005.
 2a) This action is FINAL. 2b) This action is non-final.
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 1-14 is/are pending in the application.
 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
 5) Claim(s) _____ is/are allowed.
 6) Claim(s) 1-14 is/are rejected.
 7) Claim(s) _____ is/are objected to.
 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9) The specification is objected to by the Examiner.
 10) The drawing(s) filed on _____ is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892)	4) <input type="checkbox"/> Interview Summary (PTO-413)
2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail Date. _____ .
3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date _____ .	5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152)
	6) <input type="checkbox"/> Other: _____ .

DETAILED ACTION

This Office action is in response to the RCE filed November 14, 2005.

1. The rejection as given in the previous Final rejection of June 13, 2005 over SHIOTA et al 6,190,833 is withdrawn in view of the arguments by applicant wherein the claimed crosslinking agent (B-1) is not seen to be taught wherein the phenol compound has a phenolic hydroxyl group.

Claim Rejections - 35 USC § 103

2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

3. Claims 1-14 are rejected under 35 U.S.C. 103(a) as being unpatentable over TAO 6,977,131 B2.

The claimed invention is drawn to the following as seen below:

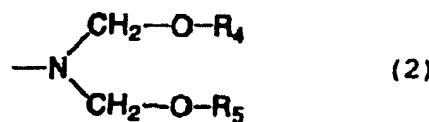
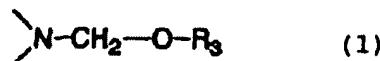
1. (currently amended): A negative resist composition comprising:

(A) an alkali-soluble resin;

(B-1) a cross-linking agent capable of cross-linking with the alkali-soluble resin (A) by the action of an acid, in which the cross-linking agent is a phenol compound containing: at least one phenolic hydroxyl group; in the molecule one or more benzene rings in the molecule; and at least two cross-linking groups bonded to any of the benzene rings, the cross-linking group being a group selected from the group consisting of a hydroxymethyl group, an alkoxyethyl group and an acyloxyethyl group;

(B-2) a cross-linking agent capable of cross-linking with the alkali-soluble resin (A) by the action of an acid, in which the cross-linking agent contains at least two groups selected from the group consisting of the groups represented by the following formula-formulae (1) and represented by the following formula-(2); and

(C) a compound capable of generating an acid upon irradiation with an actinic ray or radiation:



wherein R₃ represents a hydrogen atom, an alkyl group, or an alkylcarbonyl group; and R₄ and R₅ each represent-represents a hydrogen atom, an alkyl group or an alkylcarbonyl group.

TAO discloses a radiation sensitive patterning composition wherein the composition comprises at least one crosslinking agent, a polymer capable of reacting with the crosslinking agent, an infrared absorbing compound and a polymer having an acid generating compound.

TAO lacks a working example using the claimed crosslinking agent having the structure of formula (1) or (2), namely a crosslinking agents having an alkoxylated melamine as claimed for (B-2).

Applicants are directed to column 5, lines 23 – column 6, lines 46 which discloses suitable crosslinking agents used as ingredient (B) in TAO wherein the list includes compounds having hydroxymethyl groups, alkoxymethyl groups and vinyl ether groups. Specific compounds include resol resins as well as alkoxymethylated glycouril groups, such as melamines and alkoxylated glycourils. The crosslinking agents as disclosed in TAO can be used alone or in combination of two or more as recited in column 6, line 45-46. This the skilled artisan is clearly motivated to use a combination of the cited crosslinking agents and reasonably expect same or similar results as disclose for excellent curing and sensitivity.

It would have been *prima facie* obvious to one of ordinary skill in the art of photosensitive negative working resist compositions to use two crosslinking agents as disclosed in Example 4 substituting an alkoxymethylated melamine for the terephthaliccarboxaldehyde in Example 4 and reasonably expect same or similar results as recited for excellent sensitivity and curing rate as motivated and directed by the disclosure of TAO in column 6, lines 45 and 46.

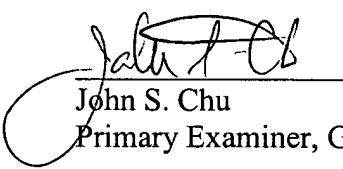
4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

Art Unit: 1752

If attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor, Cynthia Kelly, can be reached on (571) 272-1526

The fax phone number for the USPTO is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PMR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



John S. Chu

Primary Examiner, Group 1700

J.Chu

February 2, 2006